



Docket No.: M4065.0959/P959

(PATENT)

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:

Dean A. Klein

Application No.: 10/796,111

Confirmation No.: 2460

Filed: March 10, 2004

Art Unit: 2818

For:

POWER MANAGEMENT CONTROL

AND CONTROLLING MEMORY

REFRESH OPERATIONS

Examiner: Not Yet Assigned

## **INFORMATION DISCLOSURE STATEMENT (IDS)**

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Dear Sir:

Pursuant to 37 CFR 1.56, 1.97 and 1.98, the attention of the Patent and Trademark Office is hereby directed to the references listed on the attached PTO/SB/08. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the references be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is filed within three months of the U.S. filing date (37 CFR 1.97(b)(1)).

Pursuant to United States Patent and Trademark Office Official Gazette Notice: 05 August 2003 ("Information Disclosure Statements May Be Filed Without Copies of U.S. Patents and Published Applications in Patent Applications filed after June 30, 2003") copies of the U.S. Patent Document references (i.e., references AA-AU7) on the PTO/SB/08 are not provided. Copies of the Foreign Patent Document references (i.e.,

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references BA, BB, and BC) and the Other Prior Art – Non Patent Literature Document References (i.e., references CA – CO6) on the PTO/SB/08 are provided.

In accordance with 37 CFR 1.97(g), the filing of this Information Disclosure Statement shall not be construed to mean that a search has been made or that no other material information as defined in 37 CFR 1.56(a) exists. In accordance with 37 CFR 1.97(h), the filing of this Information Disclosure statement shall not be construed to be an admission that any patent, publication or other information referred to therein is "prior art" for this invention unless specifically designated as such.

It is submitted that the Information Disclosure Statement is in compliance with 37 CFR 1.98 and the Examiner is respectfully requested to consider the listed references.

The Director is hereby authorized to charge any deficiency in the fees filed, asserted to be filed or which should have been filed herewith (or with any paper hereafter filed in this application by this firm) to our Deposit Account No. 04-1073, under Order No. M4065.0959/P959. A duplicate copy of this paper is enclosed.

Dated: June 10, 2004

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Under the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it contains a valid OMB control number. Complete if Known Substitute for form 1449A/PTO 10/796,111 Application Number INFORMATION DISCLOSURE Filing Date March 10, 2004 STATEMENT BY APPLICANT First Named Inventor Dean A. Klein Art Unit 2818 (use as many sheets as necessary) **Examiner Name** Not Yet Assigned Sheet M4065.0959/P0959 2 of 13 Attorney Docket Number AS1 4,320,191 3/1982 Yoshikawa et al. AT1 4,405,710 9/1983 Balasubramanyam et al. AU1 4,419,421 12/1983 Wichelhaus, et al. AV1 4,499,557 2/1985 Holmberg et al. AW1 4,671,618 06/1987 Wu et al. AX1 4,795,657 1/1989 Formigoni et al. AY1 4,800,526 01/1989 Lewis AZ1 4,847,674 7/1989 Sliwa et al. AA2 5,177,567 1/1993 Klersy et al. AB2 |5,219,788 6/1993 Abernathey et al. AC2 5,238,862 8/1993 Blalock et al. Nagasubramanian et al. AD2 5,272,359 12/1993 AE2 5,314,772 5/1994 Kozicki AF2 5,315,131 5/1994 Kishimoto et al. AG2 5,350,484 9/1994 Gardner et al. 11/1994 AH2 |5,360,981 Owen et al. Al2 5,500,532 AJ2 5,512,328 3/1996 Kozicki et al. 4/1996 Yoshimura et al. AK2 5,512,773 4/1996 Wolf et al. AL2 5,726,083 3/1998 Takaishi AM2 5,751,012 5/1998 Wolstenholme et al. AN2 5,789,277 8/1998 Zahorik et al. AO2 5,814,527 9/1998 Wolstenholme et al AP2 5,818,749 10/1998 Harshfield AQ2 5,841,150 11/1998 Gonzalez et al. AR2 |5,846,889 12/1998 Harbison et al. AS2 5,851,882 12/1998 Harshfield AT2 5,869,843 2/1999 Harshfield AU2 5,920,788 Reinberg 7/1999 AV2 5,998,066 12/1999 Block et al. AW2 6,031,287 2/2000 Harshfield 6/2000 AX2 |6,072,716 Jacobson et al. AY2 6,077,729 AZ2 6,177,338 6/2000 Harshfield 1/2001 Liaw et al. AA3 6,117,720 9/2000 Harshfield AB3 6,143,604 11/2000 Chiang et al. AC3 6,236,059 5/2001 Wolsteinholme et al. AD3 6,297,170 10/2001 Gabriel et al. AE3 6,300,684 10/2001 Gonzalez et al. AF3 6,316,784 11/2001 Zahorik et al. AG3 | 6,329,606 12/2001 Freyman et al. AH3 |6,350,679 2/2002 McDaniel et al. Al3 6,376,284 4/2002 Gonzalez et al. AJ3 6,388,324 5/2002 Kozicki et al. AK3 6,391,688 Gonzalez et al. 5/2002 AL3 6,414,376 7/2002 Thakur et al. AM3 6,418,049 7/2002 Kozicki et al. AN3 6,420,725 7/2002 Harshfield

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Examiner	Date
Signature	Considered

<sup>\*</sup>EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant

Applicant's unique citation designation number (optional). <sup>2</sup> See attached Kinds Codes of USPTO Patent Documents at <a href="www.uspto.gov">www.uspto.gov</a> or MPEP 901.04. <sup>3</sup> Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). <sup>4</sup> For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the application number of the patent document. <sup>5</sup> Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. <sup>6</sup> Applicant is to place a check mark here if English language Translation is attached.

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				Application Number	10/618,824		
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	STATEMENT I	3Y /	APPLICANT	First Named Inventor	Terry L. Gilton		
				Group Art Unit	N/A		
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Under the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it contains a valid OMB control number. Complete if Known Substitute for form 1449B/PTO **Application Number** 10/618,824 INFORMATION DISCLOSURE July 14, 2003 Filing Date STATEMENT BY APPLICANT Terry L. Gilton First Named Inventor N/A Group Art Unit (use as many sheets as necessary) Examiner Name Not Yet Assigned 7 13 M4065.1006/P1006-A Sheet of Attorney Docket Number

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Under the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it contains a valid OMB control number. Complete if Known Substitute for form 1449B/PTO Application Number 10/618,824 INFORMATION DISCLOSURE July 14, 2003 Filing Date STATEMENT BY APPLICANT First Named Inventor Terry L. Gilton Group Art Unit N/A (use as many sheets as necessary) **Examiner Name** Not Yet Assigned

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				Group Art Unit	N/A	
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11	<b>NFORMATION</b>	1 DI	SCLOSURE	Filing Date	July 14, 2003	
l s	STATEMENT E	3Y /	APPLICANT	First Named Inventor	Terry L. Gilton	
				Group Art Unit	N/A	
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Sheet	13	of	13	Attorney Docket Number	M4065.1006/P1006-A	

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Examiner	Date	
Signature	Considered	

<sup>\*</sup>EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

<sup>&</sup>lt;sup>1</sup>Applicant's unique citation designation number (optional). <sup>2</sup>Applicant is to place a check mark here if English language Translation is attached.